According to the second method for fabricating an organic thin film of the present invention, the undercoating film made of silicon nitride or silicon nitride oxide is wet-cleaned and then organic thin film with a thickness of about 100nm or thinner is formed on the undercoating film by the use of an organic material containing at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate. Then, compared with the conventional organic thin film fabrication method that does not use an organic material containing the above solvent, coating unevenness is unlikely to show up in the resulting organic thin film even when an organic material of low viscosity is employed and therefore the uniformity of the thickness of the organic thin film can be improved. When the organic thin film is formed as a resist film or anti-reflection film, it becomes thereby possible to make the resist pattern finer. Then it also becomes possible to provide electronic devices of finer design rules.

On Page 7, Second Full Paragraph, continuing through Page 8, First Partial Paragraph

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A third method for fabricating an organic thin film according to the present invention comprises the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate; irradiating far ultraviolet ray onto the undercoating film;, and forming an organic thin film with a thickness of about 100nm or thinner on the undercoating film onto which far ultraviolet ray has been irradiated by turning the substrate and providing a liquid organic material onto the substrate; wherein the organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactat6, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate.

According to the third method for fabricating an organic thin film of the present invention, after far ultraviolet ray is irradiated onto the undercoating film made of silicon nitride or silicon nitride oxide formed on the substrate, an organic a thin film with a thickness of about 100nm or thinner is formed on the undercoating film by the use of an organic material containing at least one solvent selected from the group consisting, of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate. Then compared with the conventional organic thin film fabrication method that does not conduct far ultraviolet ray irradiation on the undercoating film or use an organic material containing the above solvent, coating unevenness is unlikely to show up in the organic thin film even when an organic material of low viscosity is employed. Therefore, the uniformity of thickness of the organic thin film can be improved. When the organic thin film is formed as a resist film or anti-reflection film, it becomes possible to make fine resist patterns. Then it becomes also possible to provide electronic devices of finer design rules.

A2 cont'd

On Page 25, Fourth Full Paragraph, continuing on Page 26, First Partial Paragraph

In the second embodiment, propylene glycol monomethyl ether acetate was used as the solvent for the organic material in the fabrication of the organic thin film 19. If the organic material for use in forming the organic thin film 19 contains at least one solvent of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate, the same effect as that obtained in this embodiment is provided. On the other hand, if cyclohexanone, diglyme or methyl isobutyl ketone is used as the solvent for the organic material in toning the organic thin film 19, the same effect as that of the present embodiment was not provided and coating unevenness was recognized in the fabricated organic thin film.

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